

“Complementi di Fisica”
Lecture 9



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Trieste, 31-10-2006

Course Outline - Reminder

- The physics of semiconductor devices: an introduction
 - Basic properties; energy bands, density of states
 - Equilibrium carrier concentration (“intrinsic”, “extrinsic”)
 - Carrier transport phenomena (summary)
- Quantum Mechanics: an introduction
 - Reminder on waves
 - Waves as particles and particles as waves (the crisis of classical physics); atoms and the Bohr model
 - The Schrödinger equation and its interpretation
 - (1-d) Wave packets, uncertainty relations; barriers and wells
 - (3-d) Hydrogen atom, angular momentum, spin
 - Systems with many particles
- Advanced semiconductor fundamentals (bands, etc...)



Lecture 9 - outline

- Summary: Generation, Recombination, Continuity
 - Left over: Quasi-Fermi Levels
- High field effects
 - Saturation of drift velocity, velocity for two-valley semiconductors
 - Avalanche processes and ionization rate
- (Thermionic extraction, tunnel effect etc: see later)



Generation, recombination, continuity: summary

Generation, Recombination, Continuity - 1

Net recombination rate (2)

$$U_n = R_n - G_n$$

$$U_p = R_p - G_p$$

For instance Photogener. G_L

minority excess Δn_p (Δn_p); approximations:
 1-dimensional, Electric field ~ 0 ,
 Uniform doping $n_0 \neq n_0(x)$, $p_0 \neq p_0(x)$,
 Low-injection, photogeneration G_L only

Table 3.3 Carrier Action Equation Summary.

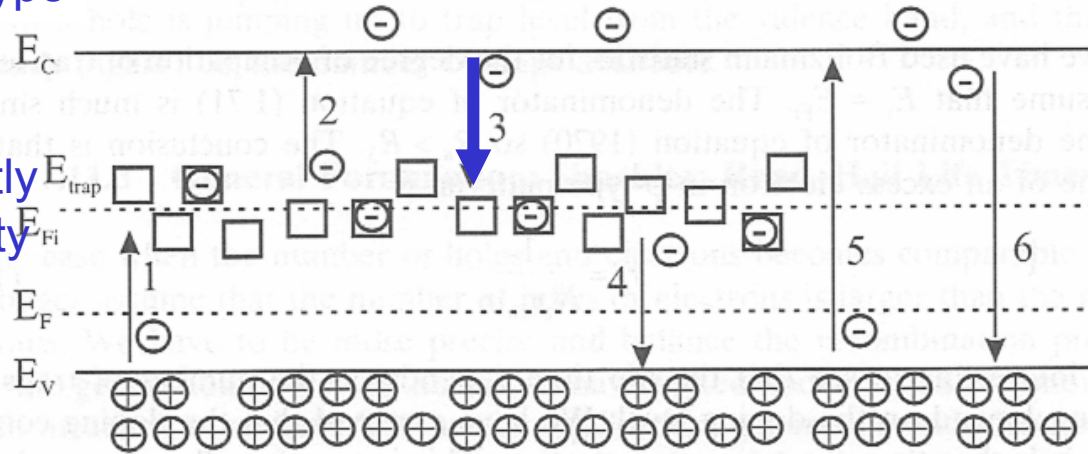
General	Equations of State "minority diffusion" approx.
$\frac{\partial n}{\partial t} = \frac{1}{q} \nabla \cdot \mathbf{J}_N + \left. \frac{\partial n}{\partial t} \right _{\text{thermal R-G}} + \left. \frac{\partial n}{\partial t} \right _{\text{other processes}}$ $\frac{\partial p}{\partial t} = -\frac{1}{q} \nabla \cdot \mathbf{J}_P + \left. \frac{\partial p}{\partial t} \right _{\text{thermal R-G}} + \left. \frac{\partial p}{\partial t} \right _{\text{other processes}}$	$\frac{\partial \Delta n_p}{\partial t} = D_N \frac{\partial^2 \Delta n_p}{\partial x^2} - \frac{\Delta n_p}{\tau_n} + G_L$ $\frac{\partial \Delta p_n}{\partial t} = D_P \frac{\partial^2 \Delta p_n}{\partial x^2} - \frac{\Delta p_n}{\tau_p} + G_L$
Current and R-G Relationships	lifetime approx. (1)
$\mathbf{J}_N = \mathbf{J}_{N \text{drift}} + \mathbf{J}_{N \text{diff}} = q\mu_n n \mathcal{E} + qD_N \nabla n$ <p style="text-align: center;"> \Downarrow drift \Downarrow diffusion </p> $\mathbf{J}_P = \mathbf{J}_{P \text{drift}} + \mathbf{J}_{P \text{diff}} = q\mu_p p \mathcal{E} - qD_P \nabla p$ $\mathbf{J} = \mathbf{J}_N + \mathbf{J}_P$	$\left. \frac{\partial n}{\partial t} \right _{\text{i-thermal R-G}} = -\frac{\Delta n}{\tau_n}$ $\left. \frac{\partial p}{\partial t} \right _{\text{i-thermal R-G}} = -\frac{\Delta p}{\tau_p}$



(1) “Low-injection minority lifetime” approximation

p-type

mostly empty



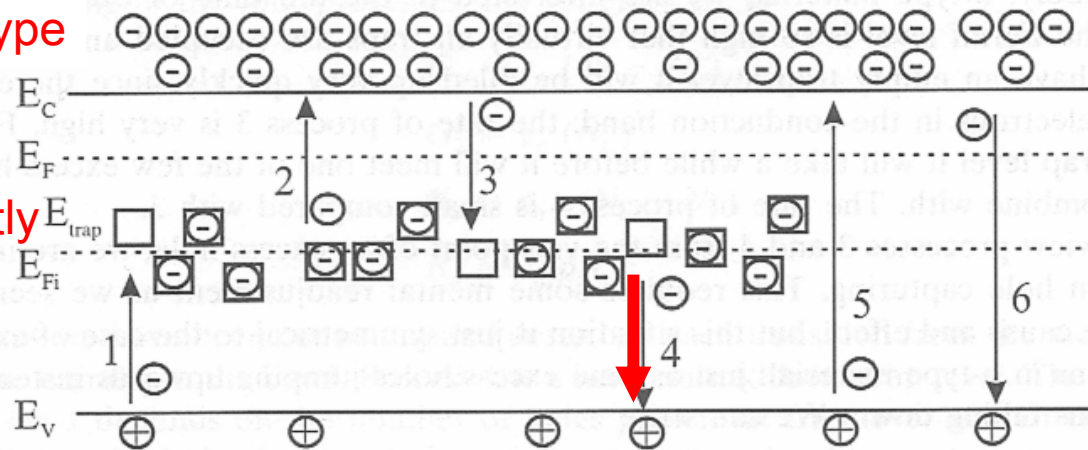
p-type semiconductor:
electron lifetime dominated
by “electron capture” (3)
in “empty” RG centers

$$U \approx v_{th} \sigma_n N_t (n_p - n_{p0})$$

$$\tau_n \equiv \frac{1}{v_{th} \sigma_n N_t} \approx 1.0 \mu\text{s (Si)}$$

n-type

mostly full



n-type semiconductor:
hole lifetime dominated
by “hole capture” (4)
in “full” RG centers

$$U \approx v_{th} \sigma_p N_t (p_n - p_{n0})$$

$$\tau_p \equiv \frac{1}{v_{th} \sigma_p N_t} \approx 0.3 \mu\text{s (Si)}$$



(2) General: “Shockley-Read-Hall” lifetimes

- What happens if these approximations are not valid?
 - n, p may be comparable (no longer true that $n \gg p$ or $p \gg n$)
 - carrier lifetime no longer dominated by availability of:
 - p-type**: “empty” traps for “electron capture” ($N_t^0 = N_t(1-F) \approx N_t$)
 - n-type**: “full” or “ionized” traps for “hole capture” ($N_t^- = N_t F \approx N_t$)
- All four “indirect” processes must be taken into account (see also SZE 2.4.2, “indirect recombination”)
 - 4 processes in the previous figure, notation compared to SZE 2.4.2:

1=d “hole emission” (from a trap)	$G_1 = e_p(N_t - N_t^-)$	$R_d = e_p N_t(1 - F)$
2=b “electron emission” (from a trap)	$G_2 = e_n N_t^-$	$R_b = e_n N_t F$
3=a “electron capture” (in a trap)	$R_3 = c_n n(N_t - N_t^-)$	$R_a = c_n N_t(1 - F)$
4=c “hole capture” (in a trap)	$R_4 = c_p p N_t^-$	$R_c = c_p N_t F$
 - Net recombination rates:

$$U_n = R_n - G_n = R_3 - G_2$$

$$U_p = R_p - G_p = R_4 - G_1$$



(2) General: “Shockley-Read-Hall” lifetimes

- From equilibrium conditions ($U_n = U_p = 0$)
 - emission coefficients (e_n, e_p) in terms of:
 - capture coeff. ($c_n = v_{th}\sigma_n, c_p = v_{th}\sigma_p$)

$$e_n = c_n n_1 \quad n_1 = n_i e^{(E_i - E_t)/kT}$$

$$e_p = c_p p_1 \quad p_1 = n_i e^{(E_t - E_i)/kT}$$

- In non-equilibrium steady-state ($U_n = U_p \neq 0$): see SZE eq. (63)

$$U = U_n = U_p = \frac{np - n_i^2}{\frac{1}{c_n N_t} (n + n_1) + \frac{1}{c_p N_t} (p + p_1)} = \frac{np - n_i^2}{\tau_n (n + n_1) + \tau_p (p + p_1)}$$

- This is a general result, usually implemented in device simulations
 - A special case: the previous “Low-injection minority lifetime” result
 - For very high doping concentrations, direct transitions become likely: this can be modeled by making τ_n and τ_p concentration-dependent



Generation, Recombination, Continuity - 2

minority carriers diffusion lengths

minority carrier lifetimes

Einstein relationships

Key Parametric Relationships

(el.)
(h.)

$$L_N \equiv \sqrt{D_N \tau_n}$$

$$L_P \equiv \sqrt{D_P \tau_p}$$

$$\frac{D_N}{\mu_n} = \frac{kT}{q}$$

$$\frac{D_P}{\mu_p} = \frac{kT}{q}$$

$$\tau_n = \frac{1}{c_n N_T}$$

$$\tau_p = \frac{1}{c_p N_T}$$

Resistivity and Electrostatic Relationships

$$\rho = \frac{1}{q(\mu_n n + \mu_p p)}$$

$$\rho = \frac{1}{q\mu_n N_D} \quad \dots n\text{-type semiconductor}$$

$$\rho = \frac{1}{q\mu_p N_A} \quad \dots p\text{-type semiconductor}$$

$$\mathcal{E} = \frac{1}{q} \frac{dE_c}{dx} = \frac{1}{q} \frac{dE_v}{dx} = \frac{1}{q} \frac{dE_i}{dx}$$

“band bending”

$$V = -\frac{1}{q}(E_c - E_{ref})$$

Quasi-Fermi Level Relationships

$$F_N \equiv E_i + kT \ln\left(\frac{n}{n_i}\right)$$

“Quasi-Fermi”

$$\mathbf{J}_N = \mu_n n \nabla F_N$$

$$F_P \equiv E_i - kT \ln\left(\frac{p}{n_i}\right)$$

???

$$\mathbf{J}_P = \mu_p p \nabla F_P$$



Quasi-Fermi levels: definition

- Fermi level E_F :

- Unique, and *meaningful only in equilibrium conditions* !
- Specifies both (free) electrons and holes concentrations
- For non-degenerate semiconductors (calling E_i the “intrinsic” Fermi level): one-to-one correspondence between E_F and both concentrations (n,p)

$$n = n_i e^{(E_F - E_i)/kT} \qquad p = n_i e^{(E_i - E_F)/kT}$$

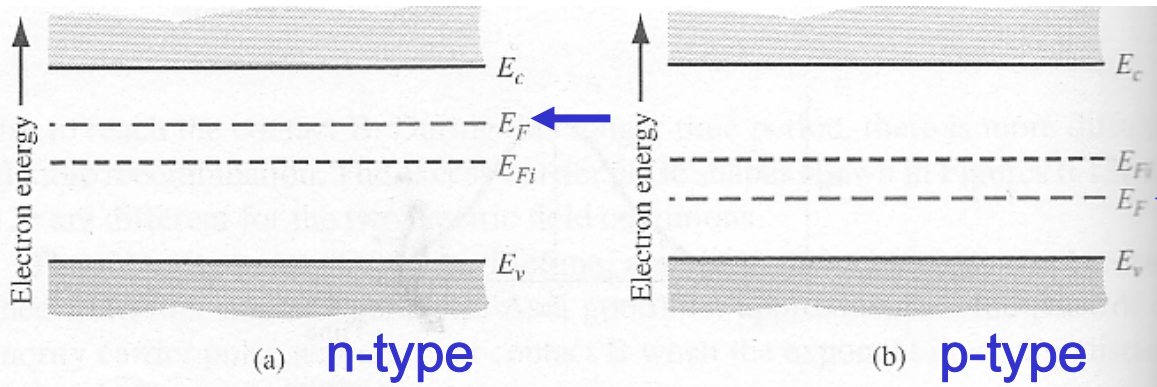
- In non-equilibrium conditions: E_F not defined! but:

- Practically convenient to deduce quickly the concentrations by inspection from the energy band diagrams
- Formally introduce *two different* “Quasi-Fermi Levels” F_N and F_P , *determined by definition* by the non-equilibrium concentrations n and p:

$$n \equiv n_i e^{(F_N - E_i)/kT} \quad \Leftrightarrow \quad F_N \equiv E_i + kT \ln(n/n_i)$$
$$p \equiv n_i e^{(E_i - F_P)/kT} \quad \Leftrightarrow \quad F_P \equiv E_i - kT \ln(p/n_i)$$

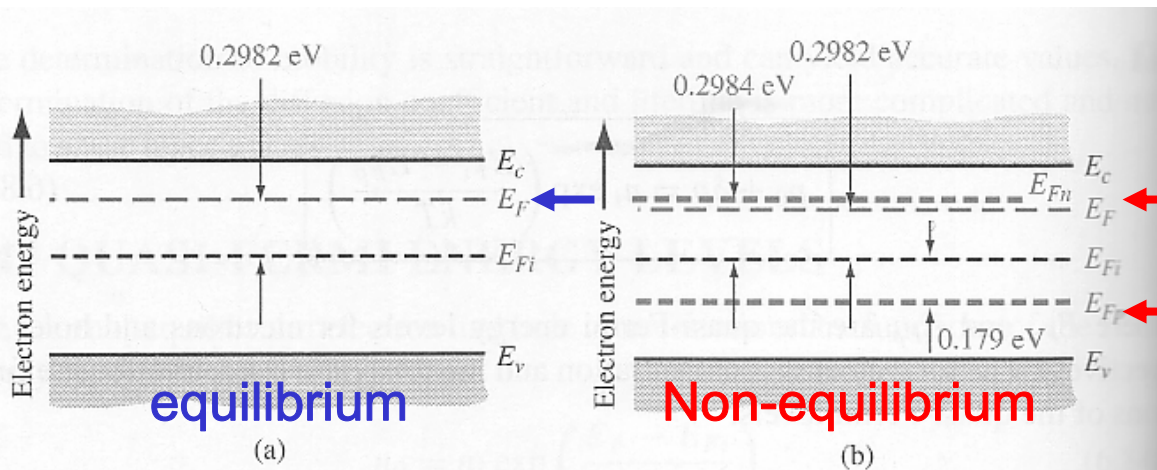


Quasi-Fermi levels: an example



Thermal equilibrium
Fermi level E_F

Figure 6.14 | Thermal-equilibrium energy-band diagrams for (a) n-type semiconductor and (b) p-type semiconductor.



Non-equilibrium
Quasi-Fermi levels
 F_N, F_P

Figure 6.15 | (a) Thermal-equilibrium energy-band diagram for $N_d = 10^{15} \text{ cm}^{-3}$ and $n_i = 10^{10} \text{ cm}^{-3}$. (b) Quasi-Fermi levels for electrons and holes if 10^{13} cm^{-3} excess carriers are present.

Quasi-Fermi levels and currents

- Interesting practical consequence: current density
 - For simplicity, one-dimensional case:

$$J_{p,x} \equiv q\mu_p p E_x - qD_p \frac{\partial p}{\partial x}$$

- Substituting the concentration $p(x)$ in terms of the quasi-Fermi level F_p (dependent on x !) and using the Einstein relationship, one obtains:

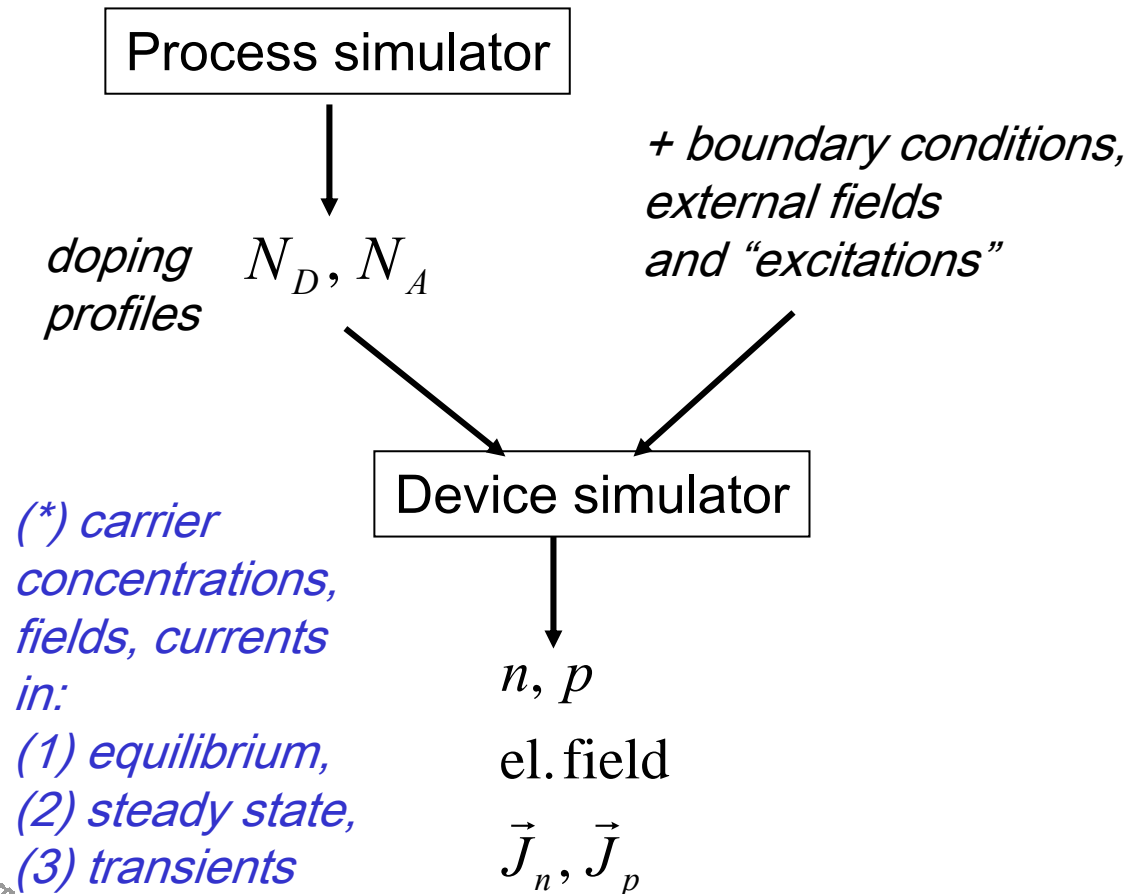
$$J_{p,x} \equiv \mu_p p \frac{\partial F_p}{\partial x} \quad \left(\text{similarly: } J_{n,x} \equiv \mu_n n \frac{\partial F_n}{\partial x} \right)$$

- A quasi-Fermi level that varies with position in a band diagram immediately indicates that current is flowing in the semiconductor! (see **exercise 9.1** for an application)



Device simulations

- In real life, device designers use programs performing numerical integrations in discrete space and time steps, to obtain (*):



$$\vec{\nabla} \cdot \vec{E} = -\nabla^2 V = \frac{\rho}{\epsilon}$$

$$\rho = -n + p - N_A + N_D$$

$$\vec{J}_n = -qn\mu_n \vec{\nabla} V + qD_n \vec{\nabla} n$$

$$\vec{J}_p = -qn\mu_n \vec{\nabla} V - qD_n \vec{\nabla} n$$

$$\frac{1}{q} \vec{\nabla} \cdot \vec{J}_n = (R - G) + \frac{\partial n}{\partial t}$$

$$\frac{1}{q} \vec{\nabla} \cdot \vec{J}_p = (R - G) + \frac{\partial p}{\partial t}$$

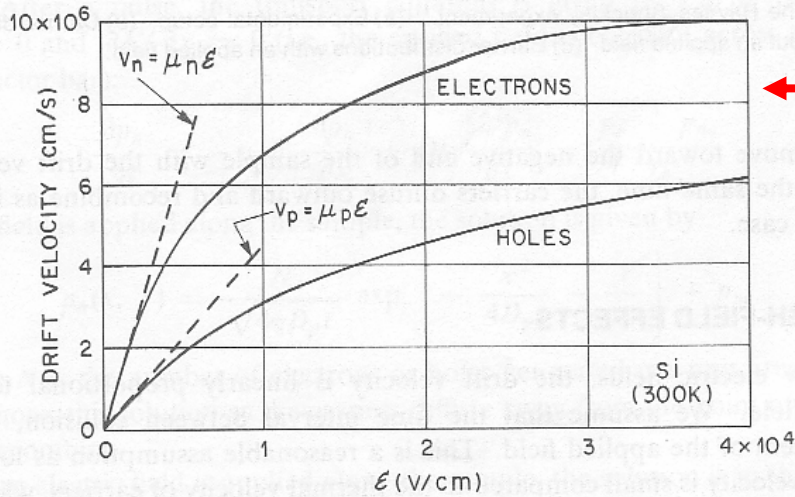


High field effects

Drift velocity saturation

Avalanche processes

Drift velocity saturation

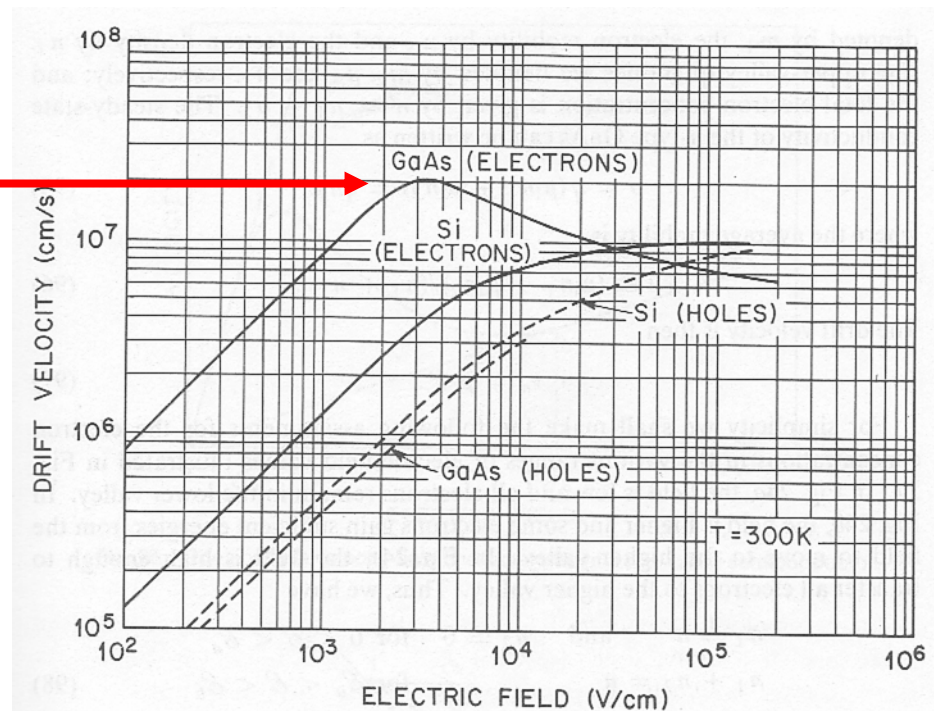


← Silicon:

- electrons and holes drift velocity
- increases linearly at small fields
- saturates (\sim thermal velocity) at high fields

GaAs:

- electrons and holes drift velocity
- Peculiar behavior
- see next slide for an explanation



Two-valley semiconductors

GaAs:

Two-valley model of
E-k band diagram:
Different effective masses
Different mobilities

$$\mu = \frac{q\tau_c}{m^*}$$

$$\sigma = q(\mu_1 n_1 + \mu_2 n_2) = qn\bar{\mu}$$

$$\bar{\mu} \equiv (\mu_1 n_1 + \mu_2 n_2) / (n_1 + n_2)$$

$$v_n = \bar{\mu}E$$

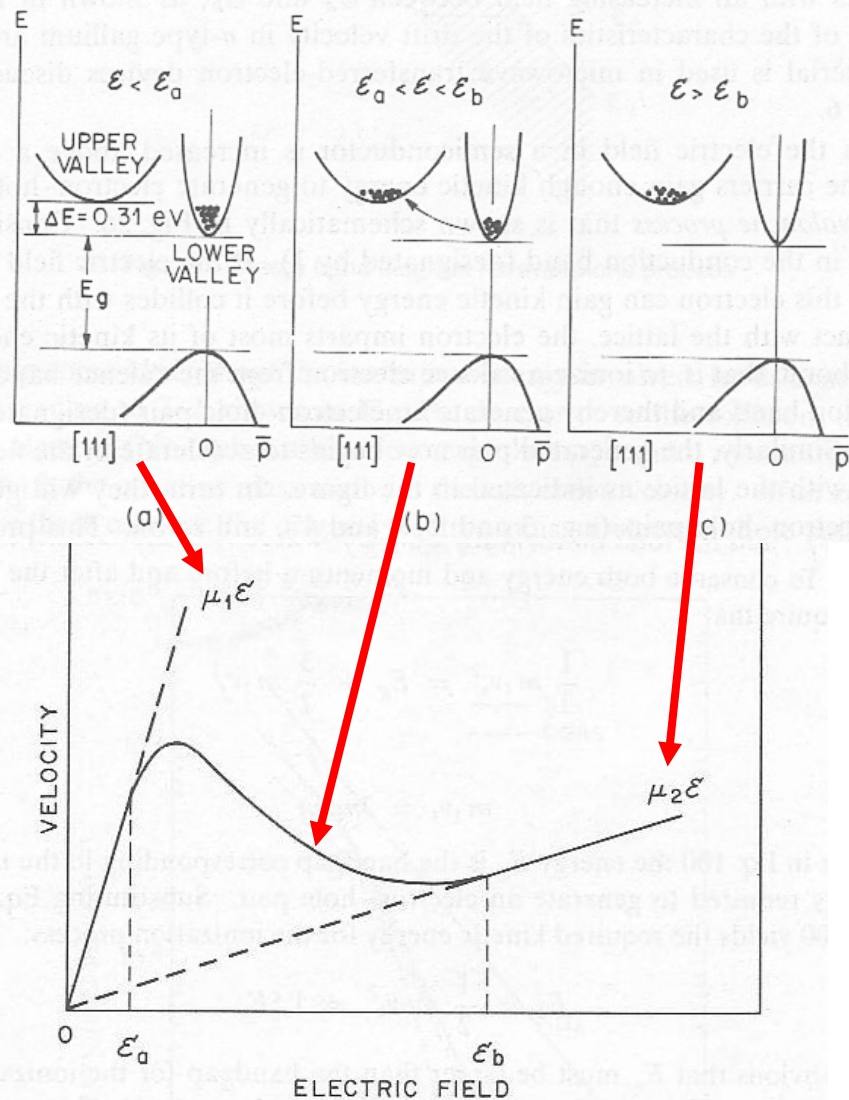


Fig. 25 One possible velocity-field characteristic of a two-valley semiconductor



Avalanche processes

To start an avalanche:
enough kinetic energy
to create an e-h pair

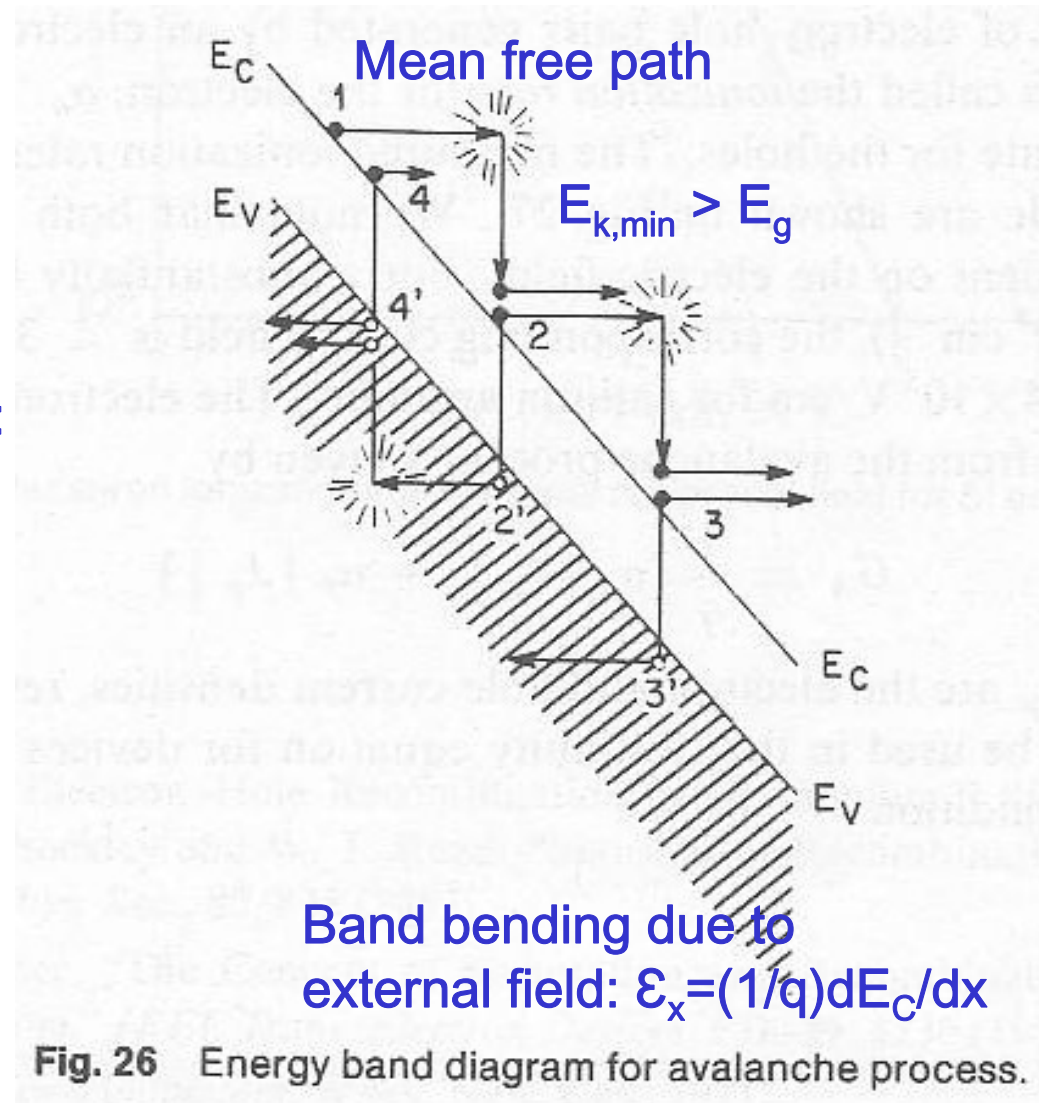
Order of magnitude estimate
from energy and momentum
conservation (process 1 → 2):

$$\frac{1}{2} m_1 v_s^2 \approx E_g + 3 \frac{1}{2} m_1 v_f^2$$

$$m_1 v_s \approx 3 m_1 v_f$$

$$E_0 = \frac{1}{2} m_1 v_s^2 \approx 1.5 E_g$$

$$G_A = \frac{1}{q} (\alpha_n |J_n| + \alpha_p |J_p|)$$



Ionization rates and generation rate

α_n, α_p ionization rates (cm^{-1})

e-h generation rate ($\text{cm}^{-3}\text{s}^{-1}$)

$$G_A = \frac{1}{q} (\alpha_n |J_n| + \alpha_p |J_p|)$$

In Silicon:

$$E_0 = 3.2 E_g \text{ (el.)}$$

$$E_0 = 4.4 E_g \text{ (h.)}$$

$$\mathcal{E} \sim 3 \times 10^5 \text{ V/cm}$$

$$\text{For } \alpha \sim 10^4 \text{ cm}^{-1}$$

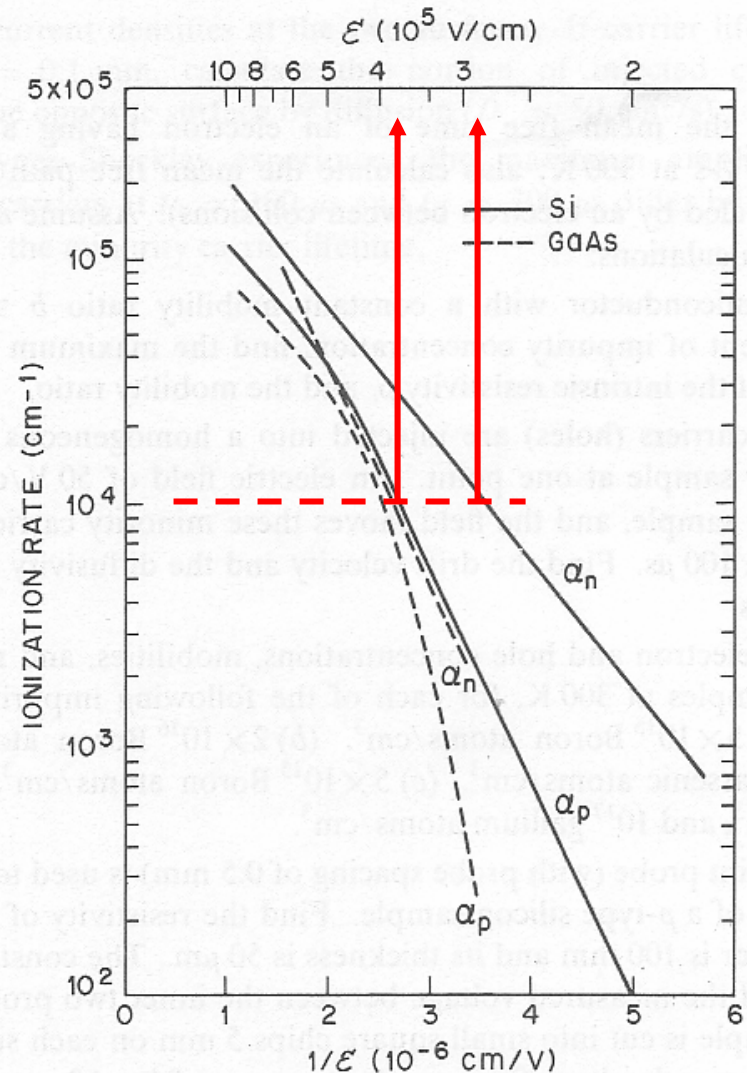


Fig. 27 Measured ionization rates versus reciprocal field for Si and GaAs.¹³



Lecture 9 - exercises

- **Exercise 9.1:** In (SZE 2.5.1), nonpenetrating illumination of a semiconductor bar was found to cause a steady state, excess-hole concentration of $\Delta p_n(x) = \Delta p_{n0} \exp(-x/L_p)$. Given low-level injection conditions, and noting that $p = p_0 + \Delta p_n$, we can say that $n \approx n_0$ and $p \approx p_0 + \Delta p_{n0} \exp(-x/L_p)$.
 - (a) Find the quasi-Fermi levels $F_N(x)$ and $F_P(x)$ as functions of x .
 - (b) Show that $F_P(x)$ is a linear function of x when $\Delta p_n(x) \gg p_0$.
 - (c) Sketch the energy band diagram under equilibrium (no illumination) and in illuminated steady-state conditions, assuming negligible electric field.
 - (d) Is there a hole current in the illuminated bar, under steady state conditions? Explain.
 - (e) Is there an electron current in the illuminated bar, under steady state conditions? Explain.

